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(71)Applicant : FUJI PHOTO FILM CO LTD

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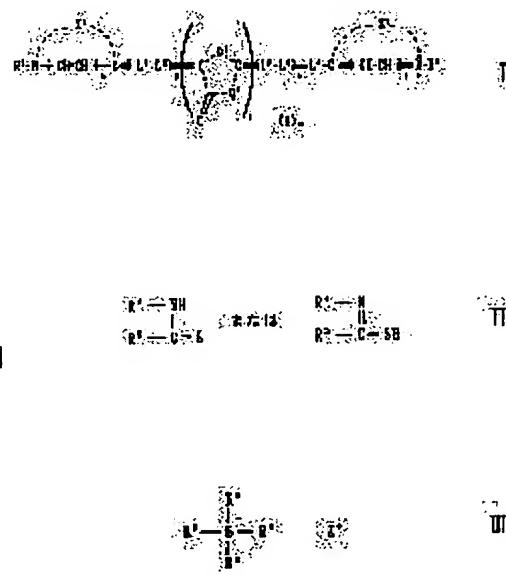
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(54) PHOTOPOLYMERIZABLE COMPOSITION

(57)Abstract:

PURPOSE: To obtain a photopolymerizable composition having high sensitivity against active ray in a wide region from ultraviolet ray to visible ray.

CONSTITUTION: This photochemical polymerizing composition contains at least one compound selected from a group consisting of: (i) polymerizable compound having an addition polymerizable unsaturated bond; (ii) a methine compound expressed in formula (I), (iii) a compound (a) having carbon-halogen bond, aromatic onium salt (b), an organic peroxide (c), a thiocompound (d) expressed in formula (II), hexaaryl biimidazole (e), a ketooxim ester (f) and a compound (g) expressed in formula (III).



LEGAL STATUS

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